Method and system for uniformly irradiating a frame of a processed substrate

ABSTRACT

A method for uniformly irradiating a frame of a processed substrate (1), said processed substrate comprising a plurality of frames, two consecutive frames being separated by an intermediate zone, said method comprises steps of:

- determining an initial position of said processed substrate using a detecting unit (80),

- comparing said detected initial position with a first predetermined position associated with a first frame of the processed substrate,

- irradiating said first frame of the processed substrate by an irradiation beam (105) emitted by a source unit (30) and scanned by a scanning unit (40) based on the first predetermined position, said irradiation beam being adapted to cover uniformly the whole first frame.

A system for uniformly irradiating a frame of a processed substrate is also described.

[Figure 3]